

REMARKS/ARGUMENTS

Favorable reconsideration of this application is respectfully requested.

The specification is amended to correct minor informalities that are not believed to raise any issues of new matter.

Claims 1 and 3-5 are pending in this application. Claim 2 is canceled by the present response without prejudice.

Claims 1-6 were rejected under 35 U.S.C. §102(b) as anticipated by U.S. patent application publication 2002/0047574 to Kojima et al. (herein "Kojima").¹ That rejection is traversed by the present response as discussed next.

Independent claim 1 is amended by the present response to clarify features recited therein, and to particularly recite certain features from dependent claim 2. Specifically independent claim 1 now recites:

wherein the high-resistance section comprises plural regions with a surface roughness of 1.0-15.0 μm , and the plural regions are disposed to increase their surface roughness sequentially from the side closer to the outer peripheral edge to the metal back layer towards the side away from the outer peripheral edge of the metal back layer.

The above-noted features are noted in the specification in different embodiments, see as non-limiting examples Figures 3, 4, and 6 in the present specification. Taking Figures 3 and 4 as a non-limiting example, a high-resistance section 9 includes plural regions 9a, 9b, 9c such that the region 9a closest to the metal back layer 7 has the greatest surface roughness, the region 9b has a lower surface roughness than the region 9a, and the region 9c farthest from the metal back layer 7 has an even further lower surface roughness than the regions 9a and 9b.

Independent claim 1 as written is directed to an image display device including a cathode substrate with an electron source for emitting electrons and an anode substrate

¹ Applicants note that grounds for rejection indicates claims 1-6 are canceled but only claims 1-5 were pending.

disposed to oppose the cathode support. The anode substrate includes a transparent substrate, a grounding section formed on the peripheral edge of the transparent substrate, a phosphor layer, a metal back layer, and a high-resistance section with plural regions with a surface roughness of 1.0-15.0 μm disposed between the metal back layer and the grounding section. The plural regions of the high-resistance section are disposed to increase their surface roughness sequentially from a side closer to the outer peripheral edge of the metal back layer towards the sides away from the peripheral edge of the metal back layer.

With the claimed structure a discharge (creeping discharge) along a plane from an outer peripheral edge of the metal back layer can be effectively suppressed and a withstand voltage characteristic can be improved.²

Kojima discloses an image display unit including a facing substrate 20 having a conductive member 80 disposed around an anode potential regulating region to which a predetermined potential is applied, a resistive film contacting the anode potential regulating region and the conductive member, and a convex projection 82 positioned between the anode potential regulating region and the conductive member 80, as shown for example in Figures 10-12.

However, Kojima does not disclose or suggest the above-noted claimed feature:

wherein the high-resistance section comprises plural regions with a surface roughness of 1.0-15.0 μm , and the plural regions are disposed to increase their surface roughness sequentially from the side closer to the outer peripheral edge of the metal back layer towards the side away from the outer peripheral edge of the metal back layer.

In addressing such features as similarly recited in dependent claim 2 the outstanding Office Action states:

...Structure 82 is between the ground 80 and the image region 12 at the plural regions on each side of the image region 12) and these regions are disposed to increase their surface

² See for example the present specification at page 8, lines 2-6.

roughness sequentially from the side close to the outer peripheral edge of the metal back layer towards the side away from it (The height (ie surface roughness) of 82 increases from the side close to the metal back layer towards the side away from it for half the distance).³

In reply to that basis for the rejection applicants note structure 82 in Kojima is clearly not "plural regions...disposed to increase their surface roughness sequentially from the side closer to the outer peripheral edge of the metal back layer towards the side away from the outer peripheral edge of the metal back layer". Region 82 in Kojima is merely a single region of convex shape.

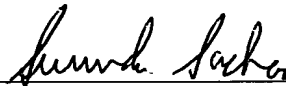
Moreover, if the outstanding rejection is citing the height of that region 82 to correspond to the resistance then it clearly cannot meet the claim limitations as the region 82 in Kojima is symmetrical so that in either direction the surface roughness would increase at the maximum height and then decrease.

In view of the foregoing comments, applicants respectfully submit amended independent claim 1 and claims 3-5 dependent therefrom, clearly distinguish over Kojima.

As no other issues are pending in this application, it is respectfully submitted that the present application is now in condition for allowance, and it is hereby respectfully requested that this case be passed to issue.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.



Eckhard H. Kuesters
Attorney of Record
Registration No. 28,870

Customer Number
22850

Tel: (703) 413-3000
Fax: (703) 413 -2220
(OSMMN 03/06)
SNS/rac

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Surinder Sachar
Registration No. 34,423

³ Office Action of September 22, 2006, page 3, first full paragraph.